

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. ASMMC.008AUS	APPLICATION NO. 09/452,844
INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>OCT 18 2003</i> (USE SEVERAL SHEETS IF NECESSARY)		APPLICANT Realmakers et al.	
		FILING DATE December 3, 1999	GROUP 2825

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)	
RMR	1 6,270,572	08/07/01	Kim et al.	—	—		
RMR	2 6,335,240	01/01/02	Kim et al.	—	—		
RMR	3 5,923,056	07/13/99	Lee et al.	—	—		
RMR	4 6,342,712	01/29/02	Miki et al.	—	—		

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)	
RMR	5	Materro et al., "Effect of water dose on the atomic layer deposition rate of oxide thin films." Thin Solid Films 368 (2000), pgs. 1-7

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EXAMINER	<i>Davros N. Paoligiani</i>	DATE CONSIDERED	<i>10/20/2003</i>
*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED; INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.			